Large Piezoelectric Response Induced by the Coexistence of Low-Symmetry and Self-Polarization in Li⁺-Nb⁵⁺-Doped BiFeO₃ Polycrystalline Films

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ABSTRACT: Pure BiFeO₃ (S1) and Li⁺-Nb⁵⁺-pair-doped BiFeO₃ (S2, S3, and S4) films were prepared by the radio-frequency magnetron sputtering onto the LaNiO₃-buffered Pt/Ti/SiO₂/Si substrate. The phase structure of the doped BiFeO₃ films is low-symmetry T-like phase owing to the chemical pressure induced by the substitution of larger Li⁺ and Nb⁵⁺ for smaller Fe³⁺, which is different from the pure BiFeO₃ film (high-symmetry R phase). Compared with the pure BiFeO₃ film, the dielectric, ferroelectric, and piezoelectric performances are greatly enhanced, especially for the piezoelectric response of 9 wt % Li⁺-Nb⁵⁺-doped BiFeO₃ (S3) film. The converse piezoelectric coefficient d_{33} of S3 film is 114.1 pm (V, which is comparable to that of lead based piezoelectric films



pm/V, which is comparable to that of lead-based piezoelectric films. The excellent piezoelectricity of S3 film is considered as the coupling results of low-symmetry T-like phase BiFeO₃ and upward self-polarization because the polarization vectors of the T-like phase and nanodomains rotate easily under small external stimuli. In addition, the reduced leakage currents in the doped BiFeO₃ films also contribute to the enhanced dielectric, ferroelectric, and piezoelectric performances.

1. INTRODUCTION

With the development of microelectromechanical and transducer applications, ferroelectric materials with superior piezoelectric responses have been of great interest among researchers.^{1–5} Large piezoelectric responses are usually relevant to the morphotropic phase boundaries (MPBs), as is observed in lead-based ferroelectrics.^{6–8} Among the lead-free candidates, the epitaxial BiFeO₃ thin films with strain-driven MPB and low-symmetry tetragonal- and rhombohedral-like (Tand R-like) phases have spurred great interest recently.^{9–13} Around the MPB, the relatively small-energy barriers between the low-symmetry phases, whose spontaneous polarization vector can rotate freely within a monoclinic plane, make them very susceptible to external electric field or stress, leading to a large piezoelectric response.^{14–16} Thus, BiFeO₃ provides an alternate choice for the future applications as a "green" piezoelectric material.

Apart from the mismatch stress in the epitaxial BeFeO₃ thin films, the phase transition of pure BiFeO₃ from R phase to another low-symmetry phase can also be triggered by ion substitutions, displaying an MPB characteristic with enhanced ferroelectric and piezoelectric response.^{17–20} Furthermore, it has been reported that the high leakage current density can be greatly reduced by the introduction of Mn, Ti, and Nb ions into Fe site to eliminate oxygen vacancies^{21–23} or the insertion of a buffer layer to prevent the interfacial reaction between platinum and bismuth.^{24–26} The reduced leakage current is of benefit in applying higher electric fields and switching domains so that an enhanced ferro/piezoelectric response can be expected; $^{27-29}$ however, the ion substitution in the past has been confined to single ion doping, while ion-pair doping at the same site has rarely been reported in the BiFeO₃ polycrystalline film.

Furthermore, the self-polarization phenomenon (macroscopic polarization without external electric field), where the high orientation is generally needed,^{30,31} is also considered to be responsible for large piezoelectric response because the rotation of polarization vector is easy to be realized under an external stimuli.^{32,33} On the basis of our previous reports, the optimized distribution of doped ion-pairs parallel to the (001) direction can also lead to a large piezoelectric response.^{34,35} Besides, the electric field induced by directional arrangement of ion pairs could be helpful to realize the self-polarization. In the present study, Li⁺-Nb⁵⁺-doped BiFeO₃ polycrystalline films with large piezoelectric response and upward self-polarization were prepared by the radio-frequency magnetron sputtering, and LaNiO₃ was used as the buffer layer to induce the high (001) orientation and prevent the direct contact of BiFeO₃ and Pt. For comparison, four films with different Li⁺-Nb⁵⁺ pair contents have been prepared via the same method. In addition, the effect of $\text{Li}^+\text{-Nb}^{5+}$ pair, LaNiO_3 buffer layer, and the mechanism of large piezoelectric response in Li⁺-Nb⁵⁺-pairdoped BiFeO₃ polycrystalline films are discussed.

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2. EXPERIMENTAL SECTION

The polycrystalline films of pure BiFeO3 and doped BiFeO3 with different Li⁺-Nb⁵⁺ pair contents were prepared by the radio frequency magnetron sputtering using the BiFeO₃ target with different LiNbO3 pellets. The LiNbO3 pellets were pasted on the BiFeO₃ target with silver pastes. The LaNiO₃ buffer layer was introduced on the Pt/Ti/SiO₂/Si substrate using a sol-gel technique before the growth of BiFeO₃ film, as previously reported.³⁶ A base pressure of 5.0×10^{-4} was achieved in the deposition chamber and the BiFeO₃ target with LiNbO₃ pellets was presputtered for 15 min to eliminate the surface heterogeneity. The depositions of pure BiFeO3 and doped BiFeO₃ films on the Pt/Ti/SiO₂/Si substrate with LaNiO₃ buffer layer were carried out with an RF sputtering power of 40W at 400 °C for 2 h under a 3:1 Ar/O₂ flow ratio. After the deposition, the films were cooled to the room temperature in vacuum chamber. Then, the resultant films were annealed at 550 °C for 30 min in air. The top platinum electrodes with a size of 3.14×10^{-4} cm² were deposited by DC magnetron sputtering before the electric properties testing. During electrical measurements, positive bias is defined as the current flow from the top electrode to the bottom electrode. In the present study, pure BiFeO₃, 4.5 wt % LiNbO₃-doped BiFeO₃, 9 wt % LiNbO₃-doped BiFeO₃, and 14.5 wt % LiNbO₃-doped BiFeO₃ thin films are termed S1, S2, S3, and S4, respectively.

The XRD experiments were performed using Cu K α radiation on an X'pert diffractometer at 40 kV and 40 mA, including the phase structure and rocking curve studies. The surface and cross-sectional morphologies of pure and doped BiFeO₃ thin films were characterized by atomic force microscopy (CSPM5600 of Benyuan) and scanning electron microscopy (Helios Nanolab600i), respectively. The domain structures of pure and doped BiFeO₃ thin films were obtained by the modified commercial atomic force microscope (AFM) with a piezoelectric force microscope (PFM) mode (Bruker multimode 8). The piezoelectric response signals from vertical cantilever deflection are proportional to the out-of-plane polarization. The frequency dependence of the dielectric permittivity and dielectric loss was characterized by the Agilent 4294A precision impedance analyzer at the frequencies ranging from 500 Hz to 1 MHz. The leakage current behaviors and P-E hysteresis loops of the samples were measured using a Ferroelectric Measurement System (P-LC100, Radiant Technology). The converse piezoelectric coefficients d_{33} of pure and doped BiFeO₃ thin films were characterized using a commercial scanning force microscope (CSPM5600 of Benyuan) equipped with a lock-in amplifier (model SR530, Standford Research System, Inc.) with the same method as that previously reported.4,26

3. RESULTS AND DISCUSSION

The XRD patterns of S1, S2, S3, and S4 thin films measured at room temperature are shown in Figure 1. It can be observed from Figure 1a that all of the thin films are well crystallized without detectable impurities or other phases, which indicates that LiNbO₃ has been well-doped into the perovskite BiFeO₃. Furthermore, only (010) and (020) reflections of BiFeO₃ can be clearly observed in all films except for S1 (a small portion of (110) can be found), which suggests that all of the films are highly (010)-oriented. To further evaluate the misorientation degree of S1, S2, S3, and S4 films, we show the measured and



Figure 1. (a) θ - 2θ scan XRD patterns of S1, S2, S3, and S4 thin films; the inset is the ω -scan XRD (rocking curve) patterns of S1, S2, S3, and S4 thin films. (b) Measured and fitted profiles of (020) reflections of S1, S2, S3, and S4 thin films.

Gaussian-fitted XRD rocking curves for (010) reflection in the inset in Figure 1a. The Gaussian widths (fwhm) for all of the films are about $6.5-8.5^{\circ}$, which further indicates that all of the films obtained in the present study are highly (010)-oriented. The results above suggest that LaNiO₃ buffer layer is very beneficial to the preferential nucleation of BiFeO₃, which is consistent with previous reports.³⁷

In addition, it can be found from Figure 1a that the positions of (020) reflection for S1, S2, S3, and S4 films gradually shift to a lower angel with LiNbO3 contents increasing. Taking ionic radius and valences into consideration, it is believed that both Li⁺ and Nb⁵⁺ have a larger ionic radius than that of Fe³⁺, and the substitution of Li⁺ and Nb⁵⁺ for Fe³⁺ will induce a compressive strain (chemical pressure) in the BiFeO₃ film and maintain the local charge neutrality. The compressive strain in the BiFeO₃ film caused by the Li⁺ and Nb⁵⁺ substitution is in accordance with the shifting reflection positions. Moreover, the profile of (020) reflection of S1 thin film is symmetric, while the (020) reflection profiles of doped $BiFeO_3$ (S2, S3, and S4) thin films are asymmetric. To investigate the differences above clearly, we show the measured and fitted profiles of (020) reflections (using pseudocubic coordinate system) of S1, S2, S3, and S4 films in Figure 1b. It has been well established that for the R phase of BiFeO₃ the profile of (020) reflection is singlet, whereas for the T-like phase the (020) reflection profiles are doublet.³⁸ According to the result above, it can be observed clearly from Figure 1b that the phase structure of S1 film is R because the profile of (010) reflection for S1 film is a symmetric singlet. Meanwhile, the profiles of (010) reflection for doped BiFeO₃ (S2, S3, and S4) films are asymmetric and they can split into two different peaks, indicating that a phase transition has taken place in the S2, S3, and S4 films due to the ion substitution. It has been reported that T-like can be induced by epitaxial strain⁵ or chemical pressure¹⁷ in the BiFeO₃ film. Therefore, the phase structure of S2, S3, and S4 films might be considered as a T-like phase. In other words, the phase structures of S2, S3, and S4 films undergo a change from the high-symmetry R phase to the low-symmetry T-like phase.

The surface and cross-section micrographs of S1, S2, S3, and S4 films are shown in Figure 2. It can be observed from the surface micrographs (Figure 2a,c,e,g) that all of the films exhibit dense, uniform microstructures and small surface roughness. From the cross-section micrographs (Figure 2b,d,f,h) the thicknesses of S1, S2, S3, and S4 films are 295, 280, 360, and 340 nm, respectively. Thus, all S1, S2, S3, and S4 films have a



Figure 2. Surface and cross-section micrographs of (a,b) S1 thin film, (c,d) S2 thin film, (e,f) S3 thin film, and (g,h) S4 thin film.

densely packed and homogeneous microstructure on a microscopic scale, indicating that the microstructures of S1, S2, S3, and S4 films are not affected by the doping of LiNbO₃. Meanwhile, LaNiO₃ buffer layer with a thickness of 10 nm is not observed in the SEM results, which is characterized by the X-ray reflectivity (XRR) in our previous report.³⁶ From the cross-sectional micrographs (Figure 2b,d,f,h), it is worth noting that the interface between the BiFeO₃ film and substrate (Pt) can be clearly distinguished owing to the existence of LaNiO₃ buffer layer, which is different from the direct contact between BiFeO₃ and Pt.²⁶

The dielectric properties of S1, S2, S3, and S4 films shown in Figure 3a were measured at room temperature with the frequency ranging from 500 Hz to 1 MHz. From Figure 3a, it can be observed that the dielectric constants of S1, S2, S3, and S4 films increase first and then decrease with LiNbO₃ contents increasing. More importantly, the dielectric losses of S2 and S3 films are much lower than that of pure BiFeO₃ (S1) film at a frequency ranging from 500 Hz to 1 MHz; however, the dielectric loss of S4 film, which is comparable to that of pure BiFeO₃ (S1) film, especially at low frequencies, as shown inset in Figure 3a, is much higher than that of S2 and S3 films.

To assess the leakage behavior of pure and doped BiFeO₃ film, the leakage current (*I*) versus electric field (*E*) curves of S1, S2, S3, and S4 films were investigated at room temperature, and the results are shown in Figure 3b. It is observed from Figure 3b) that pure BiFeO₃ (S1) film shows a high leakage current; meanwhile, the LiNbO₃-doped BiFeO₃ (S2, S3, and S4) films exhibit greatly reduced leakage current. The reduced dielectric loss and leakage current are caused by the following reasons: first, the substitution of Li⁺ and Nb⁵⁺ into the Fe site attributes to eliminate oxygen vacancies; second, the introduction of LaNiO₃ buffer layer prevents the interface reaction between platinum and bismuth, which is of benefit to reduce Bi deficiencies.

More importantly, it can be observed clearly from the upper inset in Figure 3b that a unidirectional conductive feature can be found in the S3 film; namely, it is conductive under positive biases and less-conductive under negative biases. To further confirm the unidirectional conductive feature, we show the corresponding currents (absolute value) of S1, S2, S3, and S4 films at 200 and -200 kV/cm in the lower inset in Figure 3b. From the lower inset figure in Figure 3b, it can be seen that the corresponding currents (absolute value) of the doped BiFeO₃ (S2, S3, and S4) films at 200 and -200 kV/cm exhibit large discrepancies, especially for the S3 film; however, for the pure BiFeO₃ (S1) film, the discrepancy is not existent. The results



Figure 3. (a) Frequency dependence of dielectric permittivity and dielectric loss; the inset is the dielectric losses of S1, S2, S3, and S4 thin films at 1 kHz. (b) I-V curves for S1, S2, S3, and S4 thin films. Upper inset is the I-V curve for S2 thin film, and lower inset is the corresponding current (absolute value) for S1, S2, S3, and S4 thin films at 200 and -200 kV/cm, respectively.

above suggest that the doped $BiFeO_3$ (S2, S3, and S4) films show a unidirectional conductive feature, while the pure $BiFeO_3$ (S1) film does not show any rectifying feature.

In general, the diode-like rectifying feature is relevant to a built-in electric field generated by the energy band bending or self-polarization effect.^{32,39} In the present system, there are no differences in the configuration of pure BiFeO₃ (S1) and doped BiFeO₃ (S2, S3, and S4) films. Therefore, the diode-like rectifying features in the doped BiFeO₃ (S2, S3, and S4) films are not caused by the energy band bending, which may be caused by the self-polarization effects. To further investigate the out-of-plane domain structures (upward or downward) of highly (010)-oriented S1, S2, S3, and S4 films, we performed the PFM image analysis without prepolarization. The representative out-of-plane PFM images recorded on the S1, S2, S3, and S4 films are shown in Figure 4, where the bright domains represent the upward polarizations and dark domains mean the downward or in-plane polarizations.

Figure 4a shows the domain structures of pure $BiFeO_3$ (S1) film; it can be clearly found that the unpoled S1 film consists of many nanodomains with different polarizations, and the portions of bright and dark domains in the S1 film are almost equal to each other.

Meanwhile, it can be seen from Figure 4b-d that the majority of the domains of the doped BiFeO₃ (S2, S3, and S4) films are oriented with the upward polarization (yellow bright). It is worth noting that the domain structures of the unpoled S3 film are almost upward polarization (close to the out-of-plane direction), as shown in Figure 4c, indicating an upward self-



500 nm

-180

-180

thin film, (c) the S3 thin film, and (d) the S4 thin film.

film, especially for the 180° domain wall, is much higher than that of domains themselves.²⁷ In the present study, the density of domain walls in the doped BiFeO₃ (S2, S3, and S4) films is much less than that of the pure BiFeO₃ (S1) film, which also

Figure 4. PFM domain structures of (a) the S1 thin film, (b) the S2

polarization phenomenon according to previous reports.³¹

contributes to the reduced leakage in the doped BiFeO₃ (S2, S3, and S4) films. Taking all of the above into consideration, it can be concluded that the diode-like rectifying features in the doped BiFeO₃ (S2, S3, and S4) films are caused by the selfpolarization effect.

In the present study, there is a large compressive strain and T-like phase in the doped BiFeO₃ (S2, S3, and S4) films as previously discussed. It has been reported that upward selfpolarizations can be derived from the inhomogeneous compressive strain.^{31,32} Therefore, the upward self-polarization formed in the doped BiFeO3 film is mainly caused by the compressive strain, which can mechanically switch the polarization of BiFeO₃ film.³² Furthermore, the local electric fields $(E_{\rm D})$ formed by the Li⁺-Nb⁵⁺ pairs may also contribute to the upward self-polarization in the doped BiFeO3 films if the pairs are in directional arrangement.

The ferroelectric polarization versus electric-field curves (P-*E* hysteresis loops) of S1, S2, S3, and S4 films shown in Figure 5a were measured at 1 kHz at room temperature. From Figure 5a, the slant P-E loop and low remnant polarization (P_r) of pure BiFeO₃ (S1) film are caused by the large leakage current and nonuniformity of domains. Meanwhile, in the doped BiFeO₃ films, the ferroelectric responses are greatly enhanced, especially for the S3 films. In addition, the sum of corresponding positive and negative coercive fields for S1, S2, S3, and S4 thin films is shown in the inset in Figure 5a. It can be observed from the inset in Figure 5a that the built-in electric fields exist in doped BiFeO₃ (S2, S3 and S4) films because of

Figure 5. (a) P-E hysteresis loops of S1, S2, S3, and S4 thin films. The inset is the sum of corresponding positive and negative coercive fields for S1, S2, S3, and S4 thin films. (b) Converse piezoelectric coefficient (d_{33}) of S1, S2, S3, and S4 thin films, where the slope (K)represents d_{33} ; the inset is the schematic of polarization rotation path of R, T, and T-like phase.

the unequal positive and negative coercive field, which is in accordance with the upward self-polarization effect. The enhanced ferroelectricities of doped BiFeO₃ films are the coupling results of reduced leakage currents and low densities of domain walls because the coupling effects allow domains to switch effectively under sufficient high electric fields.

Furthermore, the measured and linear fitted converse piezoelectric coefficients (d_{33}) of pure and doped BiFeO₃ films are shown in Figure 5b, where the slope of fitted lines represents d_{33} of the samples.^{3,4} From Figure 5b, it can be observed that the d_{33} value of pure BiFeO₃ (S1) film is only 43.0 pm/V (K_1 shown in Figure 5b). Although there are many nanodomains, the weak piezoelectric response of pure BiFeO₃ film is derived from the large leakage current and limited rotation of the spontaneous polarization vector of R phase.⁴⁰ The d_{33} value of S2 film is 84.8 pm/V (K₂ shown in Figure 5b), which is almost twice as that of S1 film. With the same film thickness of S1 and S2 films, the enhancement of piezoelectric response of S2 film compared with S1 film is derived from the low-symmetry phase induced by doping, which will be discussed later. With LiNbO₃ contents increasing, the piezoelectric response of doped BiFeO₃ films is greatly enhanced, as shown in Figure 5b. S3 film exhibits the highest d_{33} value of 114.1 pm/V (K_3 in the Figure 5b), which is comparable to that of the lead-based piezoelectric films.⁷ Similar to the dielectric and ferroelectric properties, the piezoelectric response of doped BiFeO₃ films decreases with the further increasing of LiNbO₃ contents (d_{33} value of S4 film is 76.7 pm/V). With the same thickness of S3 and S4 films, the reduced piezoelectric response

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500 nm

of S4 film is caused by the weak coupling of low-symmetry phase and self-polarization. Compared with S2 and S3 films, the degradations of dielectric, ferroelectric, and piezoelectric properties of S4 film indicate that an optimal doping content (more is not better) exists in the LiNbO₃-doped BiFeO₃ system.

It is generally acknowledged that the large piezoelectric response is related to the ease of polarization rotation or phase transition under external stimuli. In the present study, the lowsymmetry phase (T-like) is found in the doped BiFeO₃ (S2, S3, and S4) films, which can serve as a structure bridge between the R and T phases as shown inset in Figure 5b. The bridge facilitating the field-induced phase transition (R-T) can result in a large piezoelectric response in the doped BiFeO₃ film. In addition, the polarization vector of the T-like phase can rotate within a monoclinic plane, which is different from that of pure T and R phases.⁴⁰ Taking the upward self-polarization into consideration, the polarization vectors of the T-like phase and nanodomains are rotated easily to the direction of external electric field (perpendicular to substrates) under small external stimuli. The coexistences of T-like phases, nanodomains, and upward self-polarizations also contribute to the large piezoelectric response in the doped BiFeO3 films, which is in accordance with the previous reports.⁴⁰ Moreover, the reduced leakage current allows the doped BiFeO₃ films to be fully polarized, which is also helpful to the large piezoelectric response of doped BiFeO₃ films, especially for the S3 film.

4. CONCLUSIONS

In summary, pure BiFeO₃ (S1) and Li⁺-Nb⁵⁺-pair-doped BiFeO₃ (S2, S3, and S4) films were prepared by the radiofrequency magnetron sputtering on the LaNiO₃-buffered Pt/ Ti/SiO₂/Si substrate. Because of the chemical pressure induced by the substitution of larger Li⁺ and Nb⁵⁺ for smaller Fe³⁺, the phase structure of the doped BiFeO₃ films undergoes a change from the high-symmetry R phase to the low-symmetry T-like phase, which is different from the pure BiFeO₃ film (R phase). Besides, the upward self-polarization phenomena and reduced leakage current in the highly (010)-oriented LiNbO3-doped BiFeO₃ films were also studied. Taking the T-like phase, reduced leakage current, low densities of domain wall, and upward self-polarization into consideration, the doped BiFeO₃ films exhibit greatly enhanced dielectric, ferroelectric, and piezoelectric performances. It is worth noting that the S3 film shows an excellent piezoelectricity, with d_{33} value of 114.1 pm/ V, which is comparable to that of lead-based piezoelectric films.

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Notes

The authors declare no competing financial interest.

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